CORPORATE PROFILE

CVD Equipment Corporation: NASDAQ: CVV
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Date Founded: 1982
Number of Employees: ~140
Updated as of: 6/30/20

COMPANY OVERVIEW

Market Capitalization: $20,450,230
Share Price: $3.08 as of 6/30/20
Shares Outstanding: 6,639,685

CVD Equipment Corporation provides both equipment and material service products. We design, develop, and manufacture a broad range of state-of-the-art chemical vapor deposition equipment for use in research and production applications. In our wholly owned CVD Materials Corporation, we provide material process solutions to end customers, as well as use the solutions internally to provide competitive coating solutions. Our equipment is used to conduct materials research and production manufacturing for a multitude of end markets including but not limited to, defense, aerospace components, medical, semiconductors, solar cells, smart glass, lasers, LEDs, MEMS, nanomaterials and other applications. Through our application laboratory, we provide process development support and process startup assistance with the focus on *enabling tomorrow's technologies™*. Our wholly owned subsidiary CVD Materials Corporation uses our equipment to provide advanced surface treatments and coatings that serve demanding applications in biomedical, petroleum, pharmaceutical, aerospace, defense and many other industrial markets.

INVESTMENT HIGHLIGHTS

Chemical Vapor Deposition technology is used in many billion-dollar growth markets to manufacture high performance materials. CVD applies its 38 years of business and IP expertise across numerous applications and industries to accelerate the commercialization of novel technologies and provide for increased production at lower cost.

CVD, through its FirstNano® R&D and CVD production products, focuses on accelerating the research to commercialization of tomorrow's technologies. Working with innovators from universities, startups, and industrial companies, CVD helps them transition from R&D to production by providing a cost-efficient road map for their pilot, production, and system solution needs. CVD also operates an application laboratory where novel ideas and pilot system performance can be quickly and economically evaluated.

In early 2017, CVD Materials Corporation launched the acquired Tantaline® surface treatment and coating services. The Tantaline® process provides a rugged and corrosion resistant protection for critical applications.

In October 2017, CVD Materials Corporation acquired the assets including all intellectual property of MesoScribe Technologies Inc. a New York company. MesoScribe Technologies develops and provides products and services with its proprietary direct write deposition, MesoPlasma™ technology.

In November 2017, we expanded our investment in CVD Materials Corporation with a $13.9 million purchase of a 180,000 sq. ft. facility to house our materials manufacturing operations. During the third quarter 2019, the Company completed the relocation of its Mesoscribe™ facility from California into the new materials manufacturing facility. In addition, with other materials operations coming online, the Company has been increasing its marketing efforts by showcasing our new facility operations and offering material coating services to new and existing customers.

CVD's customers include global leaders in aerospace, defense, medical, petroleum, semiconductor, mems, and advanced materials research. As a result of being focused on chemical vapor deposition processes, coating services, and selling our CVD research solutions worldwide, we have the unique and diversified capability to provide solutions to many of the industrial applications presented to us, thus fueling our growth into the future.

In September 2019, CVD MesoScribe Technologies Corporation, in partnership with Pennsylvania State University, has been awarded a development grant from the U.S. Department of Energy's Advanced Research Projects Agency-Energy (ARPA-E). This award will be used to develop and demonstrate the integration of printed sensors into additively manufactured gas turbine components that operate in a high temperature combustion environment.

On the R&D front, the Company has been working on our fluid reactor technology and have received an Applied Research & Development (ARAD) award in collaboration with the Center of Biotechnology at Stony Brook University. This will help further our novel, patent pending technology on an improved Extracorporeal Membrane Oxygenation (ECMO) device. We anticipate further collaboration for this promising technology and application.